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**Cleanrooms and associated controlled environments —**

**Part 10:  
Assessment of surface cleanliness for  
chemical contamination**

*Salles propres et environnements maîtrisés apparentés —  
Partie 10: Évaluation de la propreté chimique des surfaces*





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CP 401 • Ch. de Blandonnet 8  
CH-1214 Vernier, Geneva  
Phone: +41 22 749 01 11  
Email: [copyright@iso.org](mailto:copyright@iso.org)  
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## Foreword

ISO (the International Organization for Standardization) is a worldwide federation of national standards bodies (ISO member bodies). The work of preparing International Standards is normally carried out through ISO technical committees. Each member body interested in a subject for which a technical committee has been established has the right to be represented on that committee. International organizations, governmental and non-governmental, in liaison with ISO, also take part in the work. ISO collaborates closely with the International Electrotechnical Commission (IEC) on all matters of electrotechnical standardization.

The procedures used to develop this document and those intended for its further maintenance are described in the ISO/IEC Directives, Part 1. In particular, the different approval criteria needed for the different types of ISO documents should be noted. This document was drafted in accordance with the editorial rules of the ISO/IEC Directives, Part 2 (see [www.iso.org/directives](http://www.iso.org/directives)).

Attention is drawn to the possibility that some of the elements of this document may be the subject of patent rights. ISO shall not be held responsible for identifying any or all such patent rights. Details of any patent rights identified during the development of the document will be in the Introduction and/or on the ISO list of patent declarations received (see [www.iso.org/patents](http://www.iso.org/patents)).

Any trade name used in this document is information given for the convenience of users and does not constitute an endorsement.

For an explanation of the voluntary nature of standards, the meaning of ISO specific terms and expressions related to conformity assessment, as well as information about ISO's adherence to the World Trade Organization (WTO) principles in the Technical Barriers to Trade (TBT), see [www.iso.org/iso/foreword.html](http://www.iso.org/iso/foreword.html).

This document was prepared by Technical Committee ISO/TC 209, *Cleanrooms and associated controlled environments*, in collaboration with the European Committee for Standardization (CEN) Technical Committee CEN/TC 243, *Cleanroom technology*, in accordance with the Agreement on technical cooperation between ISO and CEN (Vienna Agreement).

This second edition cancels and replaces the first edition (ISO 14644-10:2013), of which it constitutes a minor revision. The changes are as follows:

- the term class (classification, classified) changed to grade or assessment where appropriate;
- ISO 14644-1 moved from [Clause 2](#) to the Bibliography and ISO 14644-6 removed (document withdrawn);
- minor editorial changes.

A list of all parts in the ISO 14644 series can be found on the ISO website.

Any feedback or questions on this document should be directed to the user's national standards body. A complete listing of these bodies can be found at [www.iso.org/members.html](http://www.iso.org/members.html).



# Cleanrooms and associated controlled environments —

## Part 10:

# Assessment of surface cleanliness for chemical contamination

## 1 Scope

This document establishes appropriate testing processes to determine the cleanliness of surfaces in cleanrooms with regard to the presence of chemical compounds or elements (including molecules, ions, atoms and particles). This document is applicable to all solid surfaces in cleanrooms and associated controlled environments such as walls, ceilings, floors, worksurfaces, tools, equipment and devices.

**NOTE 1** For the purpose of this document, consideration is only given to the chemical characteristics of a particle. The physical properties of the particle are not considered and this document does not cover the interaction between the contamination and the surface.

**NOTE 2** This document does not include the contamination generation process or any time-dependent influences (e.g. deposition, sedimentation, ageing) or process-dependent activities such as transportation and handling. Neither does it include guidance on statistical quality-control techniques to ensure compliance.

## 2 Normative references

There are no normative references in this document.

## 3 Terms and definitions

For the purposes of this document, the following terms and definitions apply.

ISO and IEC maintain terminology databases for use in standardization at the following addresses:

- ISO Online browsing platform: available at <https://www.iso.org/obp>
- IEC Electropedia: available at <https://www.electropedia.org/>

### 3.1

#### air cleanliness by chemical concentration

##### ACC

level, expressed as an ISO grade level *N*, which represents the maximum allowable concentration of a given chemical species or group of chemical species, expressed in grams per cubic metre (g/m<sup>3</sup>)

Note 1 to entry: This definition does not include macromolecules of biological origin, which are judged to be particles.

### 3.2

#### contaminant category

common name for a group of compounds with a specific and similar deleterious effect when deposited on the surface of interest

### 3.3

#### chemical contamination

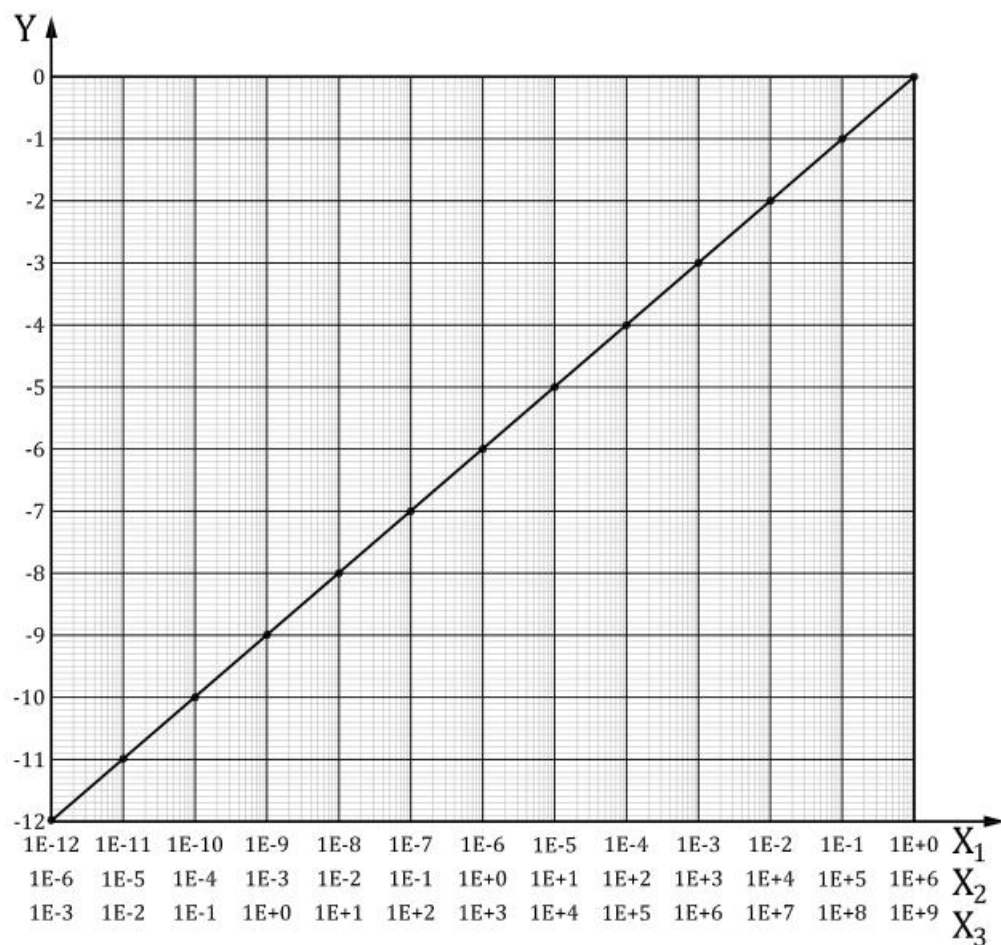
chemical (non-particulate) substances that can have a deleterious effect on the product, process or equipment

[Table 1](#) and [Figure 1](#) further illustrate the ISO-SCC designation as a function of chemical concentration on a surface.

Note also the parameters listed in [Annex B](#) that influence measured chemical levels.

**Table 1 — ISO-SCC grading levels**

ISO-SCC level	Concentration g/m <sup>2</sup>	Concentration µg/m <sup>2</sup>	Concentration ng/m <sup>2</sup>
0	10 <sup>0</sup>	10 <sup>6</sup>	10 <sup>9</sup>
-1	10 <sup>-1</sup>	10 <sup>5</sup>	10 <sup>8</sup>
-2	10 <sup>-2</sup>	10 <sup>4</sup>	10 <sup>7</sup>
-3	10 <sup>-3</sup>	10 <sup>3</sup>	10 <sup>6</sup>
-4	10 <sup>-4</sup>	10 <sup>2</sup>	10 <sup>5</sup>
-5	10 <sup>-5</sup>	10 <sup>1</sup>	10 <sup>4</sup>
-6	10 <sup>-6</sup>	10 <sup>0</sup>	10 <sup>3</sup>
-7	10 <sup>-7</sup>	10 <sup>-1</sup>	10 <sup>2</sup>
-8	10 <sup>-8</sup>	10 <sup>-2</sup>	10 <sup>1</sup>
-9	10 <sup>-9</sup>	10 <sup>-3</sup>	10 <sup>0</sup>
-10	10 <sup>-10</sup>	10 <sup>-4</sup>	10 <sup>-1</sup>
-11	10 <sup>-11</sup>	10 <sup>-5</sup>	10 <sup>-2</sup>
-12	10 <sup>-12</sup>	10 <sup>-6</sup>	10 <sup>-3</sup>



**Key**

X<sub>1</sub> surface mass concentration (g/m<sup>2</sup>)

X<sub>2</sub> surface mass concentration (µg/m<sup>2</sup>)

X<sub>3</sub> surface mass concentration (ng/m<sup>2</sup>)

Y ISO-SCC grade level

Figure 1 — ISO-SCC grade levels as a function of concentration

4.3 ISO-SCC grade level

An SCC grade level is only valid in connection with a descriptor that includes the chemical substance or group of substances for which this level number is valid. The ISO-SCC descriptor is expressed in the format ISO-SCC Level *N* (*X*), where *X* is a chemical substance or group of chemical substances.

EXAMPLE 1 With an N-Methyl-2-pyrrolidone (NMP) sample, the measured value of chemical contamination on a surface was 9,8E-7 g/m<sup>2</sup>. This is within the grade level limit of 1E-6 g/m<sup>2</sup> for Level -6. The designation would be: “ISO-SCC Level -6 (NMP).”

EXAMPLE 2 With an organic compound sample, the measured value was 6E-5 g/m<sup>2</sup> of total organic compounds (TOC). This is within the grade level limit of 1E-4 g/m<sup>2</sup> for Level -4. The designation would be: “ISO-SCC Level -4 (TOC).”

4.4 Converter for substances into surface atomic concentration

Very low concentrations are usually measured in surface number concentrations in the units of number of molecules, atoms or ions per surface area (1/m<sup>2</sup>). For grade level determination purposes, these



should be converted into surface mass concentrations in the unit mass per surface area (g/m<sup>2</sup>). This conversion is made using [Formula \(2\)](#):

$$C_{\text{SCC}} = \frac{M(C_{\text{SCC\_number}})}{N_{\text{a}}} \quad (2)$$

where

$C_{\text{SCC\_number}}$  is the surface number concentration = number of molecules, atoms or ions per surface area (1/m<sup>2</sup>);

$C_{\text{SCC}}$  is the surface mass concentration (g/m<sup>2</sup>);

$N_{\text{a}}$  is Avogadro's number (6,02 × 10<sup>23</sup>/mol);

$M$  is the molar mass of atomic, molecular or ionic species (g/mol).

For information purposes, [Figure A.4](#) in [Annex A](#) illustrates the relationship between chemical concentration on a surface (expressed in g/m<sup>2</sup>) and the atomic concentration on a surface (expressed in atoms/m<sup>2</sup>) for typical substances.

## 5 Measuring the cleanliness of surfaces for chemical contamination and demonstration of grade level compliance

### 5.1 Criteria for good cleanliness assessment

[Figure D.2](#) in [Annex D](#) illustrates how to measure different types of contamination, showing differing sampling and measuring methods.

Tests performed to demonstrate compliance shall be conducted in a laboratory environment where the airborne chemical contaminant and the airborne particle contaminant levels do not negatively influence the grade determination. Suitable measurement methods and calibrated instruments shall be used for all tests. The environment, measurement methods and instruments shall be agreed upon between customer and supplier.

Additional test essentials are discussed in [Annex C](#), while [Annex D](#) details measurement methods for demonstrating compliance.

The list of typical measurement methods is not exhaustive. Alternative methods that produce results with comparable accuracy may be specified by agreement between customer and supplier.

Measurement by different methods, even when those methods are correctly applied, may produce different results of equal validity.

Repeated measurements are recommended as part of the statistical approach.

Specific problems, such as concentration spikes, may occur when measuring high levels of cleanliness. Special quality-control techniques will then be required, as explained in [Figure D.4](#) in [Annex D](#).

Precautions should be taken to reduce electrostatic charge around the test zone, as electrostatic charge enhances chemical deposition onto surfaces. If the surface is neither conductive nor grounded or charge-neutralized, electrostatic charges can occur. Therefore, test results can vary.

For typical methods of measurement for testing surface cleanliness by chemical concentration, refer to [Annex D](#).



## 5.2 Documentation and reporting

### 5.2.1 Principle

Compliance with surface cleanliness chemical concentration (SCC) grade level requirement, as specified by the customer, is verified by performing measurements and by providing documentation of the results and conditions of measurement. Details for demonstrating compliance shall be agreed upon between customer and supplier in advance.

### 5.2.2 Testing

Tests performed to demonstrate compliance shall be conducted using suitable measurement methods together with calibrated instruments whenever possible.

Measurement methods for demonstrating compliance are described in [Annex D](#). The list of typical methods described is not exhaustive. The testing environment shall be agreed between customer and supplier. Alternative methods of comparable accuracy also may be specified by agreement between customer and supplier.

Measurement by different methods, even when correctly applied, may produce different results of equal validity.

Repeated measurements are recommended.

The testing environment should be agreed between customer and supplier.

### 5.2.3 Test report

The results from testing each surface shall be recorded and submitted as a comprehensive report, together with a statement of compliance or non-compliance to the required SCC grade level. The test report shall include as a minimum the following:

- a) name and address of the testing organization;
- b) name of the person performing the test;
- c) measurement environment;
- d) date, time and duration of sampling;
- e) time of measurement;
- f) a reference to this document, i.e. ISO 14644-10:2022;
- g) clear identification of the location of the surface measured and specific designations for coordinates of the surface, if applicable;
- h) surface cleanliness by chemical concentration level with designation expressed as SCC grade level *N*;
- i) acceptance criteria for the clean surface if agreed between customer and supplier;
- j) specified measurement method(s), equipment resolution and detection limits;
- k) details of the test procedure used, with any available data describing deviations from the test procedure (if agreed);
- l) identification of the instrument(s) used and current calibration certificate(s);
- m) number of measurements performed;

- n) test results, including chemical concentration(s) data for given substances, for all measurements performed;
- o) surface condition, i.e. after final cleaning, before or after packaging, with agreement on type and quality of packaging required.

An example of how this test report may be constructed can be found in [Annex E](#). Other variations of the test report which are agreeable to both the customer and supplier may be used.

## Annex A (informative)

### Conversion between different unit expressions of surface concentration for chemical substances

#### A.1 Principle

In addition to the unit of surface mass concentration of  $\text{g}/\text{m}^2$ , there exist several different units to express surface number concentration of an organic compound or a group of organics such as molecules/ $\text{m}^2$ , based on a number of organic molecules, and atoms  $\text{C}/\text{m}^2$ , based on a number of atoms of carbon composing organic compound(s) under consideration for each contaminant category.

#### A.2 Examples

For information purposes, [Tables A.1](#) to [A.3](#) illustrate how the different units of surface number concentrations (molecules/ $\text{m}^2$  or atoms  $\text{C}/\text{m}^2$ ) can be converted into surface mass concentrations in terms of carbon ( $\text{g C}/\text{m}^2$ ) or whole compound ( $\text{g}/\text{m}^2$ ), respectively, using the examples of heptane, hexadecane and di (2-ethylhexyl) phthalate.

**Table A.1 — Illustration of the relationship between unit of surface concentration [ $\text{g}/\text{m}^2$ ] and surface number concentration [molecules/ $\text{m}^2$ , atoms  $\text{C}/\text{m}^2$ ] for heptane ( $\text{C}_7\text{H}_{16}$ ), CAS No. 142-82-5**

	Symbol	Unit	$M = 100,2, N_c = 7$			
			Example 1	Example 2	Example 3	Example 4
Surface number molecular concentration	$C_{\text{molecule}}$	[molecules/ $\text{m}^2$ ]	1,00E+19	1,42E+18	7,16E+16	6,01E+16
Surface number concentration in terms of carbon	$C_{\text{carbon\_number}}$	[atoms $\text{C}/\text{m}^2$ ]	7,00E+19	1,00E+19	5,00E+17	4,19E+17
Surface mass concentration in terms of carbon	$C_{\text{carbon\_mass}}$	[g $\text{C}/\text{m}^2$ ]	1,39E-3	1,98E-4	1,00E-4	8,39E-6
Surface mass concentration	$C_{\text{SCC}}$	[g/ $\text{m}^2$ ]	1,66E-3	2,36E-4	1,19E-4	1,00E-6

**Table A.2 — Illustration of the relationship between unit of surface concentration [g/m<sup>2</sup>] and surface number concentration [molecules/m<sup>2</sup>, atoms C/m<sup>2</sup>] for hexadecane (C<sub>17</sub>H<sub>34</sub>), CAS No. 544-76-3**

	Symbol	Unit	<i>M</i> = 226,4, <i>N<sub>c</sub></i> = 17			
			Example 1	Example 2	Example 3	Example 4
Surface number molecular concentration	<i>C<sub>molecule</sub></i>	[molecules/m <sup>2</sup> ]	1,00E+19	6,20E+18	3,12E+16	2,60E+16
Surface number concentration in terms of carbon	<i>C<sub>carbon_atom</sub></i>	[atoms C/m <sup>2</sup> ]	1,59E+20	1,00E+19	5,00E+17	4,20E+17
Surface mass concentration in terms of carbon	<i>C<sub>carbon_mass</sub></i>	[g C/m <sup>2</sup> ]	3,19E-3	2,00E-4	1,00E-4	8,49E-6
Surface mass concentration	<i>C<sub>SCC</sub></i>	[g/m <sup>2</sup> ]	3,77E-3	2,35E-4	1,17E-4	1,00E-4

**Table A.3 — Illustration of the relationship between unit of surface concentration [g/m<sup>2</sup>] and surface number concentration [molecules/m<sup>2</sup>, atoms C/m<sup>2</sup>] for di (2-ethylhexyl) phthalate (C<sub>24</sub>H<sub>38</sub>O<sub>4</sub>), CAS No. 117-817-7**

	Symbol	Unit	<i>M</i> = 390,6, <i>N<sub>c</sub></i> = 24			
			Example 1	Example 2	Example 3	Example 4
Surface number molecular concentration	<i>C<sub>molecule</sub></i>	[molecules/m <sup>2</sup> ]	1,00E+19	4,20E+18	2,00E+16	1,50E+16
Surface number concentration in terms of carbon	<i>C<sub>carbon_atom</sub></i>	[atoms C/m <sup>2</sup> ]	2,39E+20	1,00E+19	4,89E+17	3,60E+17
Surface mass concentration in terms of carbon	<i>C<sub>carbon_mass</sub></i>	[g C/m <sup>2</sup> ]	4,89E-3	2,04E-4	1,00E-4	7,37E-6
Surface mass concentration	<i>C<sub>SCC</sub></i>	[g/m <sup>2</sup> ]	6,62E-3	2,76E-4	1,35E-4	1,00E-4

Each surface number concentration can be converted to the original surface concentration from [Formulae \(A.1\) to \(A.3\)](#):

$$C_{SCC} [g/m^2] = C_{molecule} [molecules/m^2] \times \frac{M [g/mol]}{N_a [molecules/mol]} \quad (A.1)$$

$$C_{SCC} [g/m^2] = \frac{C_{carbon\_atom} [atoms C/m^2]}{N_c [atoms C/molecule]} \times \frac{M [g/mol]}{N_a [molecules/mol]} \quad (A.2)$$

$$C_{SCC} [g/m^2] = \frac{\left[ \frac{C_{carbon\_mass} [g C/m^2]}{M_c [g/mol]} \right]}{N_c [atoms C/molecule]} \times M [g/mol] \quad (A.3)$$

where

*N<sub>c</sub>* is the number of carbon composing organic compound(s) under consideration;

*M<sub>c</sub>* is the molar mass of carbon.



Surface number concentration with different types of unit expression based on Langmuir–Blodgett (LB) film for typical organics is also listed in [Table A.4](#). The surface number concentration can be obtained from [Formula \(A.4\)](#):

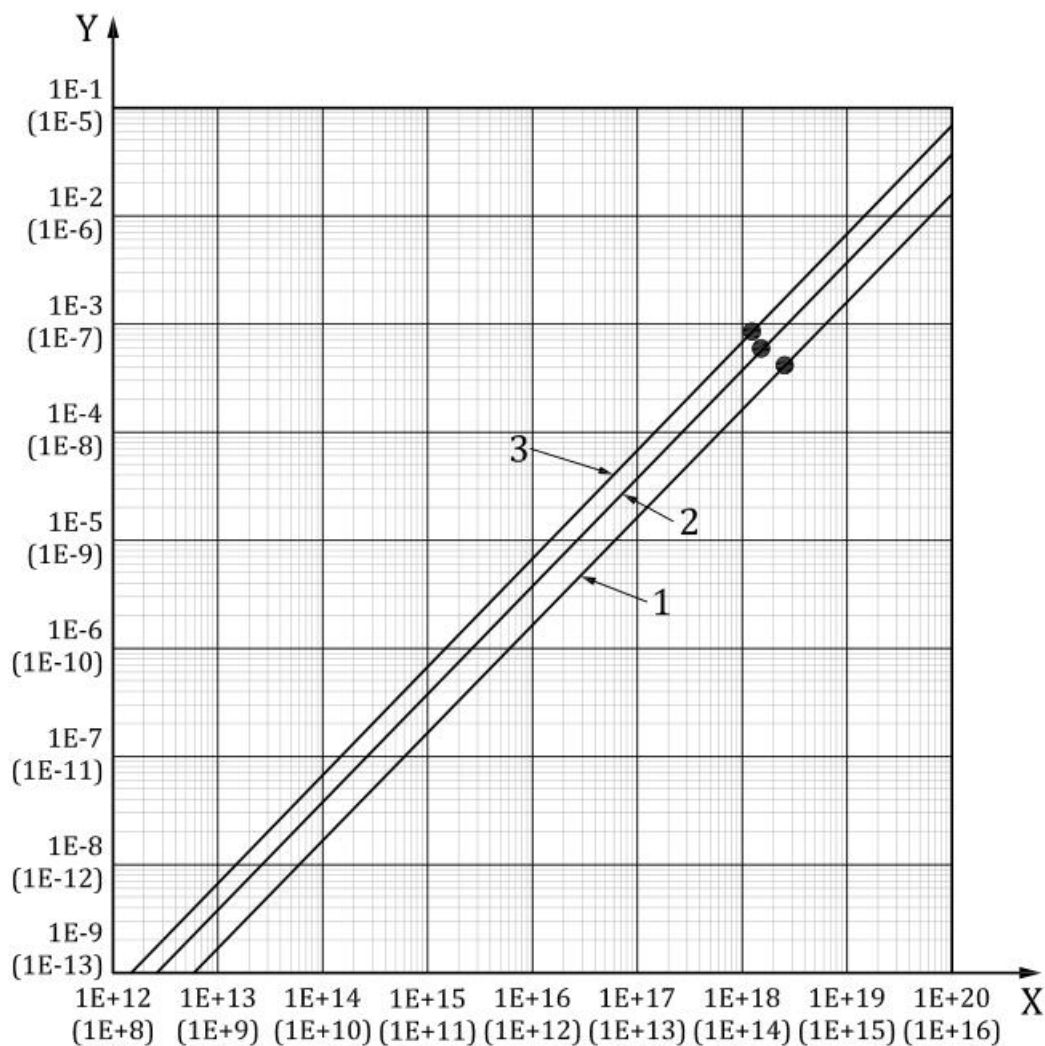
$$C_{\text{SCC\_LB}} \left[ \text{g} / \text{m}^2 \right] = (M / N_{\text{a}})^{1/3} d^{2/3} \tag{A.4}$$

where *d* is the density of organic compound(s) in g/m<sup>3</sup>.

**Table A.4 — Monolayer concentration based on Langmuir–Blodgett film**

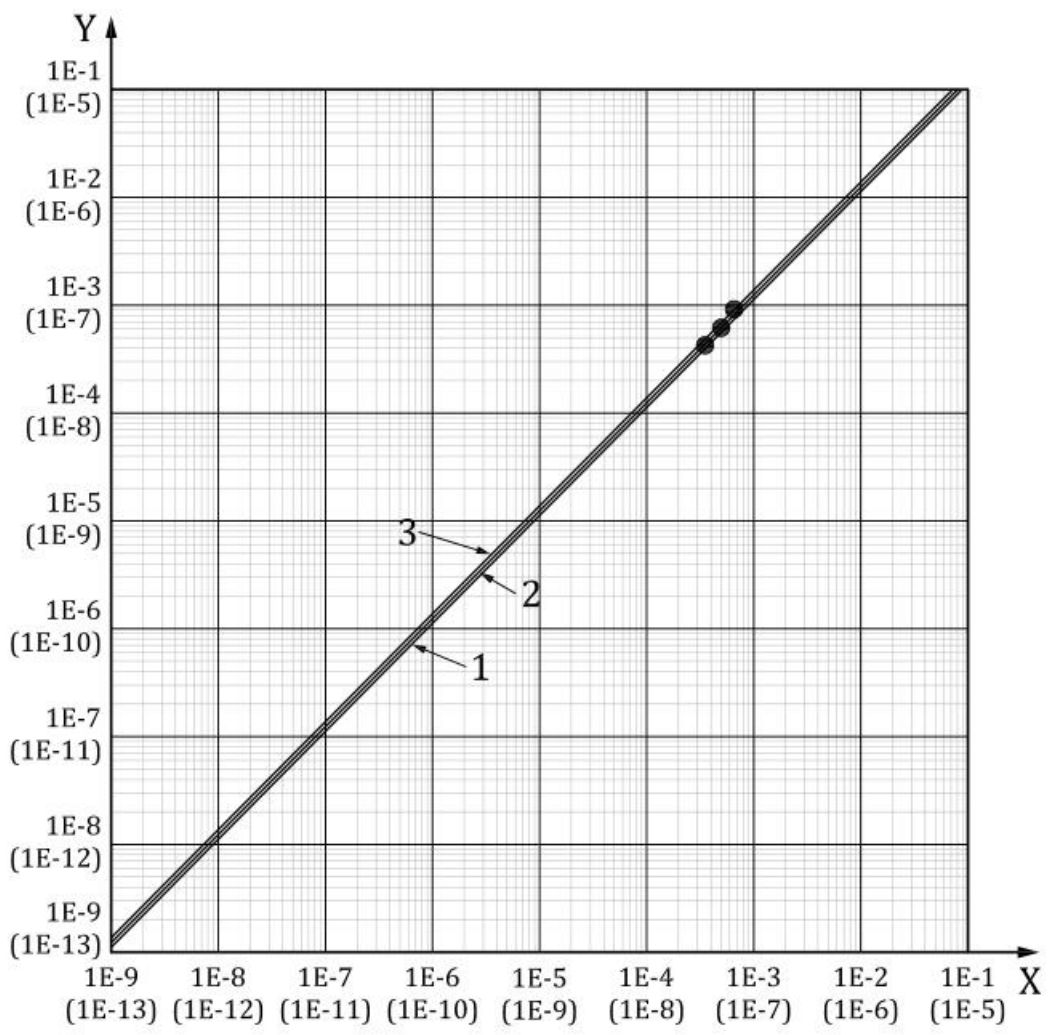
	Heptane (C <sub>7</sub> H <sub>16</sub> ), CAS No. 142-82-5	Hexadecane (C <sub>17</sub> H <sub>34</sub> ), CAS No. 544-76-3	Di (2-ethylhexyl) phthalate (C <sub>24</sub> H <sub>38</sub> O <sub>4</sub> ), CAS No. 117-817-7
Surface number molecular concentration	2,55E+18	1,62E+18	1,34E+18
Surface number concentration in terms of carbon	1,79E+19	2,59E+19	3,21E+19
Surface mass concentration in terms of carbon	3,56E-4	5,18E-4	6,56E-4
Surface mass concentration	4,24E-4	6,10E-4	8,88E-4

For information purposes, [Figures A.1](#) to [A.4](#) illustrate how the different units of surface number concentrations (molecules/m<sup>2</sup> or atoms C/m<sup>2</sup>) can be converted into surface mass concentrations in terms of carbon (g C/m<sup>2</sup>) or whole compound (g/m<sup>2</sup>), respectively.

**Key**

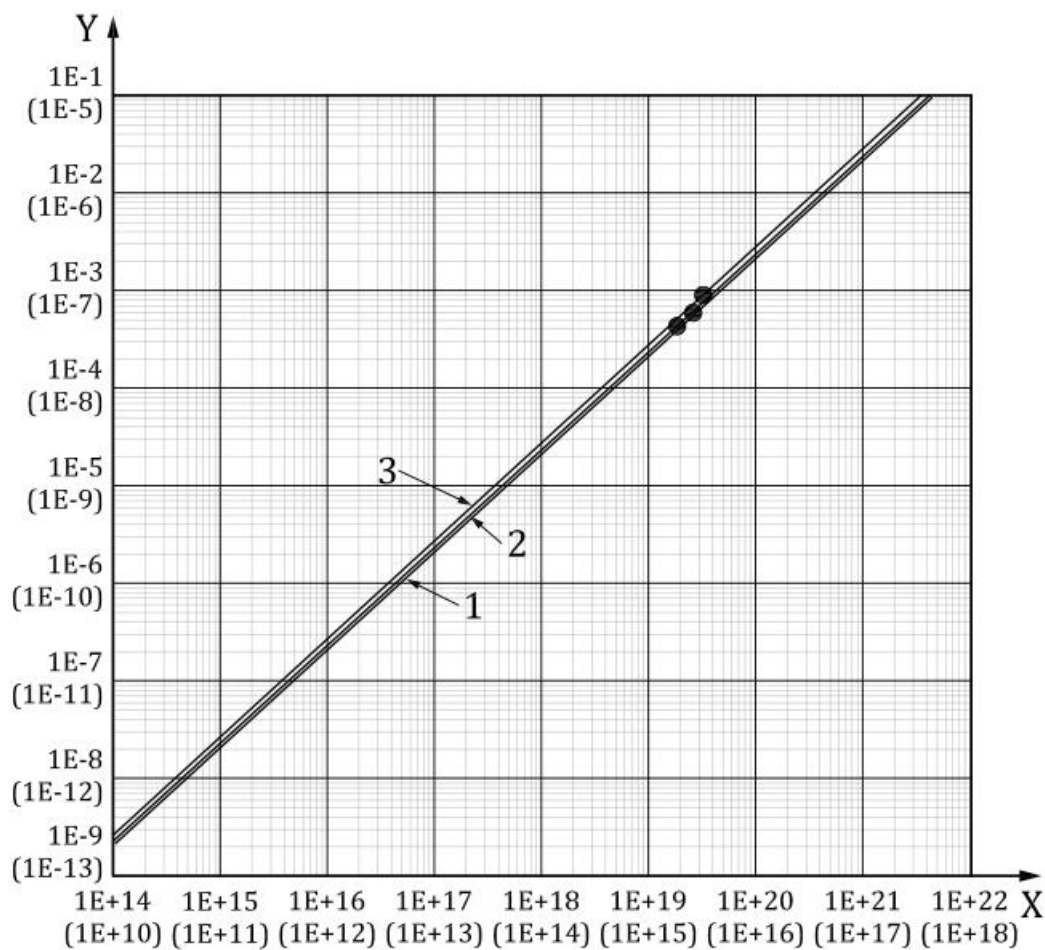
- X surface molecular concentration ( $\text{molecules/m}^2$ ) [surface molecular concentration ( $\text{molecules/cm}^2$ )]
- Y surface mass concentration ( $\text{g/m}^2$ ) [surface mass concentration ( $\text{g/cm}^2$ )]
- surface concentration corresponding to monolayer based on LB model
- 1 heptane ( $\text{C}_7\text{H}_{16}$ ), CAS No. 142-82-5
- 2 hexadecane ( $\text{C}_{17}\text{H}_{34}$ ), CAS No. 544-76-3
- 3 di (2-ethylhexyl) phthalate ( $\text{C}_{24}\text{H}_{38}\text{O}_4$ ), CAS No. 117-817-7

**Figure A.1 — The relationship between the units of surface mass concentration ( $\text{g/m}^2$ ) and surface molecular concentration ( $\text{molecules/m}^2$ ) for typical organics**



- Key**
- X surface atomic concentration in terms of mass of carbon (grams C/m<sup>2</sup>) [surface atomic concentration in terms of mass of carbon (grams C/cm<sup>2</sup>)]
  - Y surface concentration (g/m<sup>2</sup>) [surface concentration (g/cm<sup>2</sup>)]
  - surface concentration corresponding to monolayer based on LB model
  - 1 heptane (C<sub>7</sub>H<sub>16</sub>), CAS No. 142-82-5
  - 2 hexadecane (C<sub>17</sub>H<sub>34</sub>), CAS No. 544-76-3
  - 3 di (2-ethylhexyl) phthalate (C<sub>24</sub>H<sub>38</sub>O<sub>4</sub>), CAS No. 117-817-7

**Figure A.2 — The relationship between the units of surface concentration (g/m<sup>2</sup>) and surface atomic concentrations, in terms of mass of carbon (grams C/m<sup>2</sup>) for typical organics**

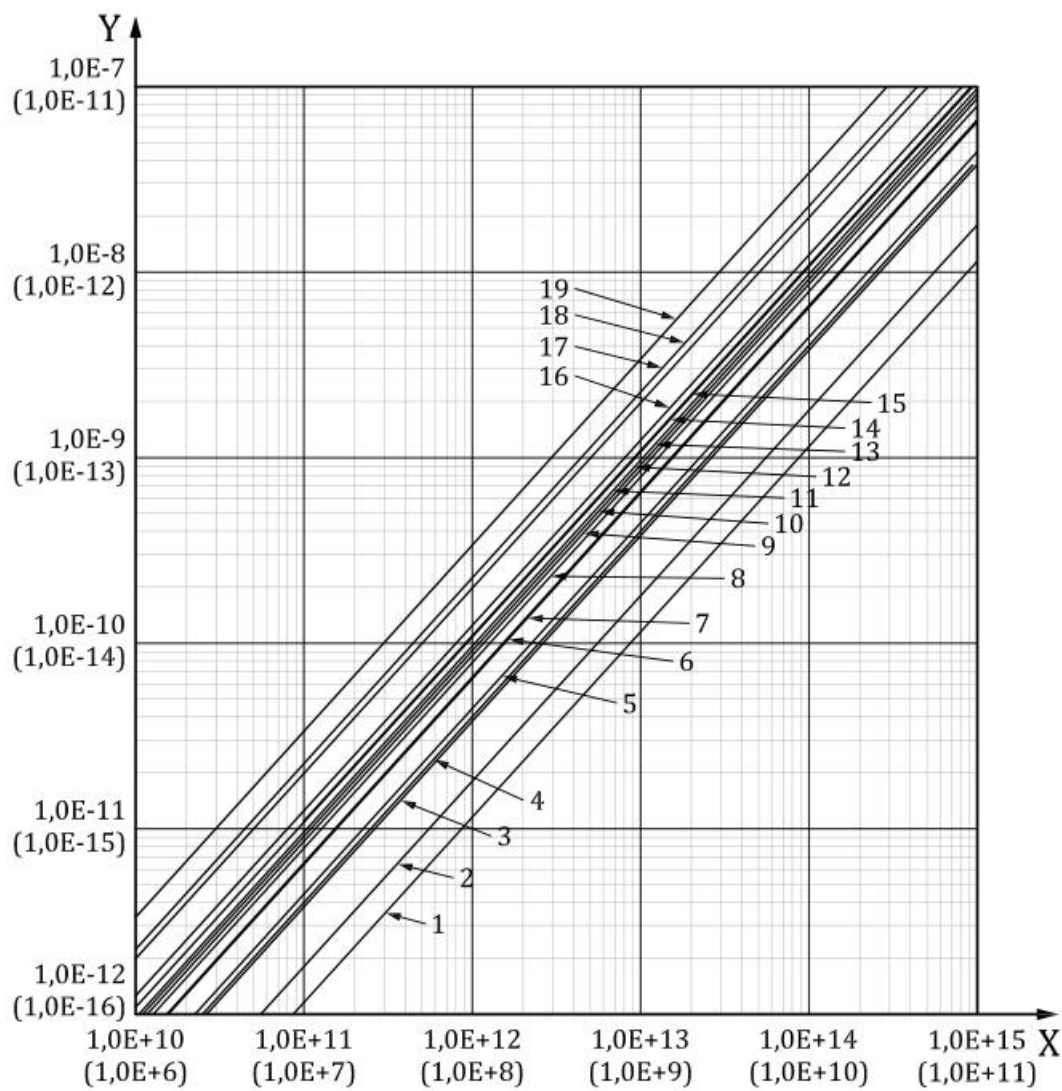


#### Key

- X surface atomic concentration in terms of numbers of carbon (atoms C/m<sup>2</sup>) [surface atomic concentration in terms of numbers of carbon (atoms C/cm<sup>2</sup>)]
- Y surface concentration (g/m<sup>2</sup>) [surface concentration (g/cm<sup>2</sup>)]
- surface concentration corresponding to monolayer based on LB model
- 1 heptane (C<sub>7</sub>H<sub>16</sub>), CAS No. 142-82-5
- 2 hexadecane (C<sub>17</sub>H<sub>34</sub>), CAS No. 544-76-3
- 3 di (2-ethylhexyl) phthalate (C<sub>24</sub>H<sub>38</sub>O<sub>4</sub>), CAS No. 117-817-7

**Figure A.3 — The relationship between the units of surface concentration (g/m<sup>2</sup>) and surface atomic concentration, in terms of numbers of carbon (atoms C/m<sup>2</sup>) for typical organics**





**Key**

X surface atomic concentration in terms of numbers of atoms (atoms/m<sup>2</sup>) [surface atomic concentration in terms of numbers of atoms (atoms/cm<sup>2</sup>)]

Y surface concentration (g/m<sup>2</sup>) [surface concentration (g/cm<sup>2</sup>)]

1 Li (M = 6,9)	8 Ti (M = 47,8)	15 Zn (M = 65,4)
2 B (M = 10,8)	9 Cr (M = 52,0)	16 As (M = 74,9)
3 Na (M = 23,0)	10 Mn (M = 54,9)	17 Sn (M = 118,7)
4 Mg (M = 24,3)	11 Fe (M = 55,9)	18 Ba (M = 137,33)
5 Al (M = 27,0)	12 Co (M = 58,9)	19 Pb (M = 207,2)
6 K (M = 39,1)	13 Ni (M = 58,7)	
7 Ca (M = 40,1)	14 Cu (M = 63,4)	

**Figure A.4 — The relationship between the units of surface mass concentration (g/m<sup>2</sup>) and surface atomic concentration in terms of numbers of atoms (atoms/m<sup>2</sup>) for typical substances**

## **Annex B**

### **(informative)**

## **Parameters influencing testing and interpretation of results**

### **B.1 Parameters**

Parameters influencing testing and interpretation of results include the following:

- a) skill level of personnel doing sampling or making the test;
- b) reliability, repeatability and capability level of the testing laboratory;
- c) cleanliness level of sample vessels, tools and test equipment;
- d) cleanliness level of packaging used for shipping the samples;
- e) use of an agreed sampling, blank and error management procedure for collecting and measuring samples (see [Figure D.3](#) in [Annex D](#));
- f) unauthorized opening of the sample;
- g) opening the sample outside a controlled environment;
- h) quality of chemical or water used to strip the chemical from its substrate;
- i) loss of analyte during sampling, shipping or testing;
- j) loss or change of analyte by desorption or thermal decomposition during test heating;
- k) failure to continually recalibrate test equipment or to investigate unusual data excursions (test spikes);
- l) errors in measuring or calculating the sample area.

### **B.2 Considerations**

The list in [B.1](#) is not comprehensive.

## **Annex C** **(informative)**

### **Essential considerations for a good cleanliness assessment**

#### **C.1 Principle**

The following considerations should be established, agreed and managed before starting and during the assessment:

- a) surface wettability state, i.e. hydrophilic or hydrophobic;
- b) substance or group of substances used in the subject material;
- c) substance or group of substances of interest used in the subject process;
- d) substance or group of substances used in the maintenance process;
- e) substance or group of substances found in the outside and inside air;
- f) existence of a general chemical, molecular or product-specific problem;
- g) substance or group of substances intended to be measured;
- h) nature, volume and velocity of the air during sampling;
- i) odour detection during sampling (precautions should be taken to prevent inhalation);
- j) temperature, relative humidity and pressure levels during sampling;
- k) visualization test or an air cleanliness by chemical concentration (ACC) measurement prior to the SCC measurement;
- l) nanoparticle measurement prior to the SCC measurement;
- m) cleaning substance or process used;
- n) expected level of the measurement result;
- o) type of measurement instrument needed;
- p) point of interest representative of the entire sample;
- q) contamination from the outside environment;
- r) recontamination from the measurement process or instrument;
- s) restriction of electrostatic discharge and electrical transients at the measurement site;
- t) measurement results within the specification of the grading level;
- u) application of adequate quality control to the collection and measurement of data.

#### **C.2 Considerations**

See [Annex D](#) for detail on measurement methods.

## Annex D (informative)

### Methods for testing surface cleanliness for chemical concentration

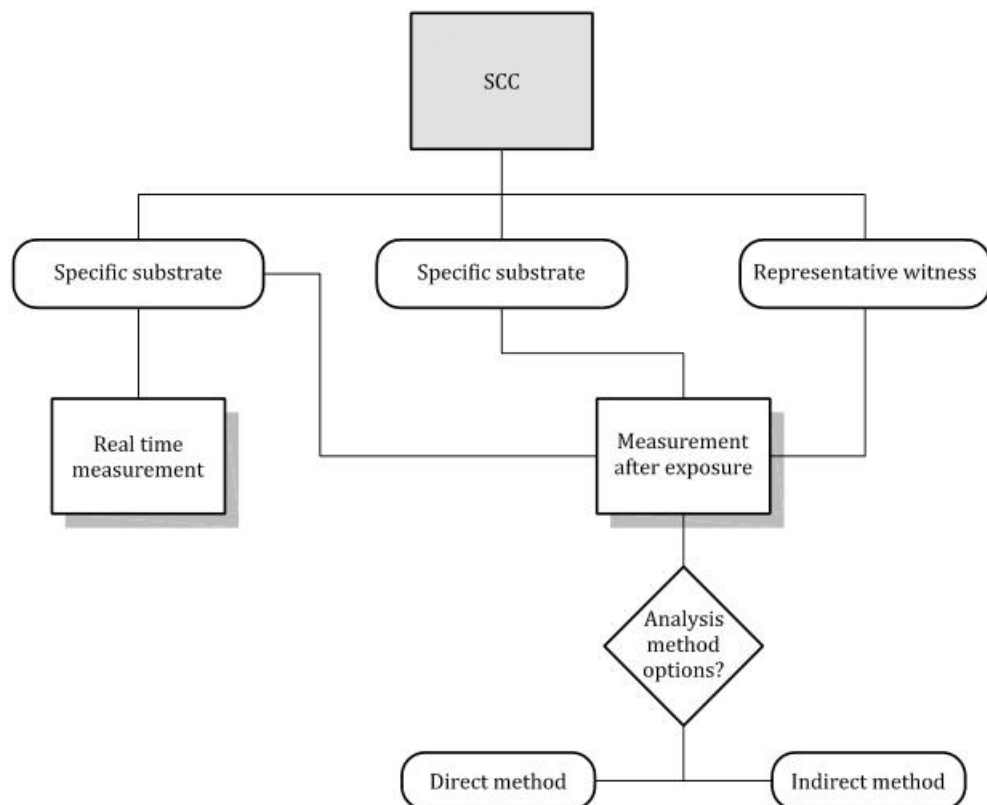
#### D.1 Method selection

##### D.1.1 Principle

In order to obtain quantitative information regarding surface cleanliness, appropriate measurement methods should be selected. In some cases where quantitative information cannot be ascertained for a surface, it is possible at least to obtain a qualitative result. Qualitative results cannot be used for surface cleanliness by chemical concentration grading level determination as defined in [Clause 5](#).

##### D.1.2 Measurement matrix

[Figure D.1](#) provides a matrix for selecting an appropriate method for measuring surface cleanliness, chemical concentration.

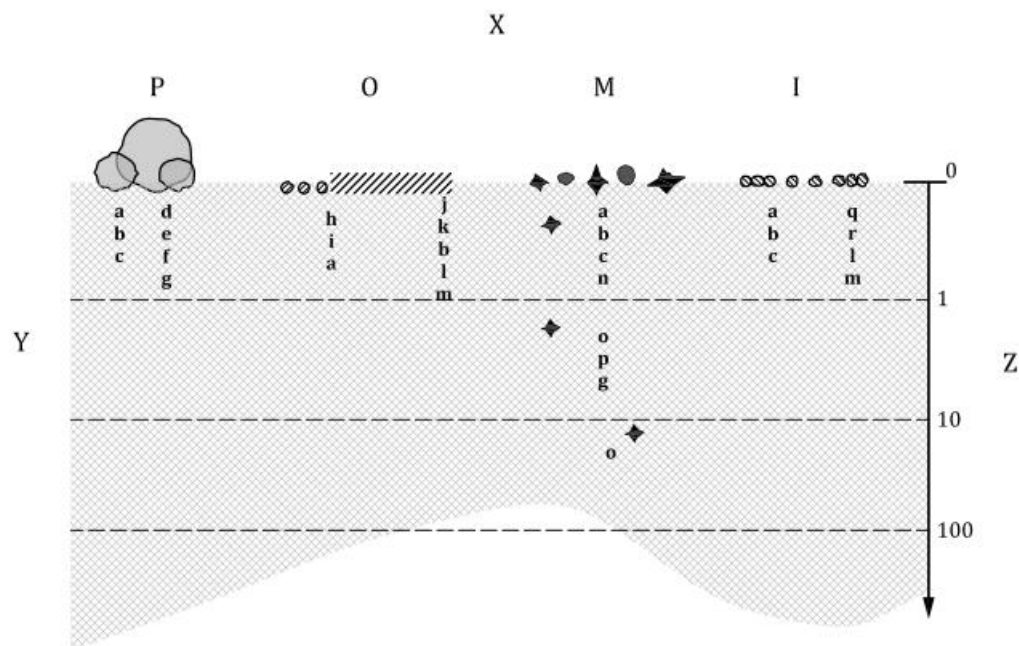


**Figure D.1 — Analysis of surface cleanliness, chemical concentration: measurement matrix chart**

##### D.1.3 General application range of principal measurement methods

[Figure D.2](#) illustrates how to measure different types of contamination, indicating which measurement methods are appropriate for measuring particular substances.





### Key

X	surface chemical contamination	
Y	main measurement methods	
Z	detection depth (nm)	
P	particles	
O	organics	
M	metals	
I	ions, i.e. acids and bases	
a	TOF-SIMS	time of flight–secondary ion mass spectrometry
b	XPS	X-ray photo-electron spectroscopy
c	AES	Auger electron spectroscopy
d	SEM	scanning electron microscopy
e	SEM-EDX	SEM–energy dispersive X-ray spectroscopy
f	SEM-WDX	SEM–wavelength dispersive X-ray spectroscopy
g	TXRF	total reflection X-ray fluorescence spectroscopy
h	TD-GC-MS	thermal desorption–gas chromatography/mass spectrometry
i	TD-IMS/MS	TD–ion mobility spectroscopy/MS
j	FTIR	Fourier transform infrared spectroscopy
k	MIR-FTIR	multiple interlayer reflection–FTIR
l	QCM	quartz crystal microbalance
m	SAW	surface acoustic wave
n	VPD-ICP/MS	vapour phase decomposition–inductive coupled plasma/MS
o	SIMS	secondary ion mass spectrometry
p	VPD-TXRF	vapour phase decomposition–TXRF
q	SE-IC/MS	solvent extraction–ion chromatography/MS
r	SE-HPLC	SE–high-performance liquid chromatography

**Figure D.2 — General application range of principal measurement methods**

## D.2 Criteria for the measurement of surface cleanliness for chemical concentration

### D.2.1 General

The grade level of surface cleanliness for chemical concentration can be determined as soon as the chemical contamination has been measured.

As a measurable and quantitative criterion for the evaluation and definition of the surface cleanliness, the number and type of all agreed adherent chemical substances should be determined.

### D.2.2 Requirements of the measurement method

The measurement method is selected according to criteria determined by the surface being tested and its characteristics. Some of the most important requirements are summarized as follows:

- a) information regarding chemical characteristics and resistance (e.g. material, concentration);
- b) feasible measuring positions (direct, real-time measuring device such as an SAW instrument);
- c) feasible measuring positions (indirect, analytical measuring device such as an SEM stub zone);
- d) testing speed and effort involved (i.e. use of random sampling or series testing);
- e) flexibility (i.e. whether the method can be rapidly implemented on various surfaces of different components);
- f) little or no surface alteration caused by the measurement procedure (i.e. measurement surfaces are not altered as a result of being wetted with flushing fluids).

Due to requirements a) to f) in [D.2.2](#), the measurement methods described in [D.2.3](#) can be categorised and limited for each of the applications.

### D.2.3 Direct or indirect measurement methods

#### D.2.3.1 Principle

Ideally, surface cleanliness for chemical concentration is best assessed when the test surface can be accessed by the chosen measurement device. In principle, the following methods can be utilized to measure the surface cleanliness:

- a) direct methods;
- b) indirect methods where a pre-treatment technique may also be introduced.

Direct methods that do not require sample pre-treatment should generally be given priority. Generally, these methods involve less measurement activity and are also associated with fewer errors, thus giving more reproducible results than indirect methods. However, depending on component and sampling feasibility for complex components, indirect methods are often the only possible alternative in order to determine the chemical cleanliness of a surface.

#### D.2.3.2 Collection method

The chemical contamination under consideration may be presented in one of three groups:

- 1) total product — where the whole contaminated specimen is sent to test;
- 2) deposition sample — from proximity exposure onto witness discs or wafers;



- 3) extracted sample — collected from materials, work tops or equipment, using appropriate physical tools such as swabs, scalpels or adhesive tapes (for inorganic contamination) of predetermined contamination level or by solvent extraction.

#### D.2.3.3 Detachment techniques

“Total product”-type contamination may be collected and analysed as per [Figure D.3](#), using either wet or dry techniques. Deposition samples may also follow the same procedure, wherein the contaminant is either displaced by surfactant in a water solution or dissolved by an organic solvent. The resulting analyte is then fed into the appropriate test system for indirect assessment. Alternatively, if “dry” assessment is to be made, the material will be cut into appropriately sized pieces and loaded directly into the instrument.

The third type – extracted samples – requires the contaminant to be transferred to adhesive tapes or SEM stubs that can be directly loaded into the instrument. Low-tack adhesive is used for this work, which involves placing the tape or stub over the surface and making firm contact with the film. The adhesive or stub is then placed in a clean, sealed transport pouch for shipment to the laboratory. Non-leaching cleanroom gloves should be used when taking the sample. Depending on the extraction method used and the contamination form, either analysis can be carried out directly by placing the physical collection sample into the analytical instrument, or further preparation by chemical or thermal techniques will be required.

#### D.2.4 Packaging of test samples

##### D.2.4.1 Packaging of samples for chemical examination

Samples that are to be assessed for SCC outside the area of origin should be packaged as follows:

- a) Preparation should take place inside the area of origin. The preparer should wear appropriate cleanroom clothing.
- b) To handle samples, a technician should wear a new pair of washed nitrile-rubber or latex cleanroom gloves and use tweezers or vacuum pickup.
- c) When a cleaning process has been used, the samples should be allowed to cool and dry before wrapping in clean aluminium foil.
- d) Each sample should be foil-wrapped separately before being placed in a cleanroom bag.
- e) Cleanroom-produced polyethylene bags with a fully detailed chemical test certificate should be used. The minimum thickness of the bags should be 80 µm to avoid tearing.
- f) The bag should be sealed with specified adhesive tape and an identity label should be fixed to the outside, worded to prevent the bag from being opened outside a controlled environment.
- g) A second cleanroom bag should then be placed over the first bag to eliminate particulate contamination.

##### D.2.4.2 Removal from packaging

- a) The exterior bag should be removed immediately before entering the controlled test environment.
- b) The interior bag should not be removed before arrival in the controlled test environment.
- c) Full cleanroom garments, including hood and face mask, should be worn when handling the interior pack.
- d) A new pair of washed nitrile-rubber or latex cleanroom gloves should be worn when examining the samples.

### D.2.5 Pre-treatment methods

In situations where a direct measurement technique is not practical, it may be necessary to condition the sample before measurement using an additional surface refinement technique. See also [Figure D.3](#).

Examples of pre-treatment are:

- a) Field-ion beam (FIB) microscopy — a preparation technique using an ion beam to create a cross-section in the specimen which is then analysed using a high-resolution microscope, such as a scanning electron microscope (SEM), a transmission electron microscope (TEM) or a scanning transmission electron microscope (STEM).
- b) Thermal desorption (TD) spectroscopy — the contaminant is thermally evaporated into a gaseous substance, which is then analysed using controlled analytical methods. Derivatives of this are:
  - TD-GC-MS, used on inorganic and metallic surfaces where the final analysis is carried out using gas chromatography with mass spectrometry;
  - TD-QMS, using thermal desorption and measuring ion intensity with a quadrupole mass spectrometer;
  - TD-API-MS, using a thermally desorbed atmospheric pressure ionization mass spectrometer;
  - wafer thermal desorption (WTD), used for semiconductor wafers.
- c) Solvent extraction (SE) — a suitable solvent is used to dissolve the surface contaminant creating a test solution for use in one of the following wet microanalysis methods:
  - solvent dissolution (SD), where both the contaminant and the substrate matrix are dissolved by the solvent for a few nanometres depth, as shown in [D.2.8](#);
  - vapour phase decomposition (VPD), where the contaminant is dissolved using vaporized hydrofluoric acid and tested as shown in [D.2.8](#).

### D.2.6 Comparative test methods

The following tables are for guidance only and are not intended to be exhaustive or comprehensive. [Table D.1](#) lists direct test methods and [Table D.2](#) lists indirect methods, which may include pretreatment.

### D.2.7 Direct measurements

Complex methods: X/Y (for example, GC-MS), where X is the main measuring method to be used and chromatographic separation (qualification) and determination (quantification) are the basic functions. The assessment is based on the 'X' process. 'Y' describes the additional functions, for example sensitivity of mass spectrometry for each chromatogram peak to make up quantification. Additional information for 'X', such as a chromatogram or the mass spectra of each peak to ascertain qualification, may also be shown.



Table D.1 — Direct measurement methods and their applications

Technique	Acronym	Principle	Information gained	Sensitivity	Depth resolution	Lateral resolution	Quantitative analysis?	Typical applications
Auger electron spectroscopy	AES	Method in which an electron spectrometer is used to measure the energy distribution of Auger electrons emitted from a surface	Structure composition	0,1 at %	< 10 nm	20 nm	Semi-quantified with standard materials	Characterization of surface contaminants; multilayer structure
X-ray photo-electron spectroscopy (also known as electron spectroscopy for chemical analysis)	XPS (or ESCA)	Method in which an electron spectrometer is used to measure the energy distribution of photoelectrons and Auger electrons emitted from a surface irradiated by X-ray photons	Quantified elemental and oxidation state	0,1 at %	< 10 nm	< 10 µm	Semi-quantified with standard materials	Surface analysis of organic and inorganic materials or residues; depth profiling for thin-film composition; oxide thickness measurements (SiO <sub>2</sub> , Al <sub>2</sub> O <sub>3</sub> ); determination of functional polymer groups
Secondary ion mass spectrometry	SIMS	Mass spectrometry is used to measure the mass-to-charge quotient and abundance of secondary ions emitted from sample after ion bombardment	Elemental, simple inorganic molecules	ppm-ppb	10 nm	30 nm	Quantified with standard materials	Trace contamination of surfaces, thin films, multilayer structures and interfaces; composition and impurity measurements of thin films
Time-of-flight secondary ion mass spectrometry	TOF-SIMS	Same as SIMS	Elemental and molecular	ppm-ppb	< 5 nm	< 0,2 µm	Semi-quantified with standard materials	Microanalysis of organic and inorganic materials; mass spectra direct from surfaces; ion surface imaging
NOTE Resolution and sensitivity are interdependent parameters. Resolution is related to the concentration on the sample. Sensitivity can be influenced by optimizing the sample area.								

Table D.1 (continued)

Technique	Acro- nym	Principle	Information gained	Sensitiv- ity	Depth resolu- tion	Lateral resolu- tion	Quan- titative analysis?	Typical ap- plications
Scanning electron microscopy	SEM	High-power microscope using a focused scanned electron beam to produce images	Structure and morphology	N/A	N/A	N/A	N/A	Characterization of micro-structural surface topography, grain size, oxides and contamination
Energy-dispersive X-ray spectroscopy	SEM EDX	Analytical capability that uses a solid-state cooled detector system to detect and measure X-ray pulses emitted during SEM interaction	Elemental; may be combined with imaging tools (SEM, TEM, STEM)	0,1 %	$\cong 1 \mu\text{m}$	$\cong 1 \mu\text{m}$	yes	Elemental microanalysis
Total reflection X-ray fluorescence spectroscopy	TXRF	X-ray spectrometer measuring energy distribution of fluorescent X-rays emitted from surface irradiated by primary X-rays under condition of total reflection	Quantified elemental	10 ppb	1 nm	1 mm	Quantified with standard materials	Qualitative elemental screening of unknown samples, metallic surface contamination on semiconductor wafers, composition ratios of binary thin films
Fourier transform infrared spectroscopy	FTIR	Measurement for infrared absorption spectra in which a spectrometer is used to measure the infrared energy	Chemical bonding and molecular structure	$1\text{E-}19$ carbon atoms/ $\text{m}^2$	0,1–2,5 $\mu\text{m}$	10–100 $\mu\text{m}$	Quantified with standards	Identification of molecular structure organic compounds, films, particles, powders liquids; quantification of O and H in Si wafers; quantification of H in SiN wafers

NOTE Resolution and sensitivity are interdependent parameters. Resolution is related to the concentration on the sample. Sensitivity can be influenced by optimizing the sample area.

Table D.1 (continued)

Technique	Acronym	Principle	Information gained	Sensitivity	Depth resolution	Lateral resolution	Quantitative analysis?	Typical applications
Multiple internal reflection FTIR	MIR-FT-IR	Optically modified version of FTIR; low-angle incident IR is multi-reflected between infrared transparent prism and substrate surface to enhance detection activity	As above	Less than $1\text{E-}18$ carbon atoms/ $\text{m}^2$	As above	As above	As above	Similar to above on surfaces
Quartz crystal microbalance	QCM	Device in which piezoelectric quartz crystals respond to the condensation of gases by reducing operating Hz in a linear mass-to-Hz relationship	Molecular flux measurement	$\text{ng}/\text{cm}^2\text{-Hz}$	N/A	N/A	Vibration frequency is compared with reference materials of known concentration	Thin film deposits of gaseous contaminants onto quartz detector surface
Surface acoustic wave detector	SAW	Item as above	Molecular flux measurement	$0,01 \text{ ng}/\text{cm}^2\text{-Hz}$	N/A	N/A	Acoustic wave is compared with reference materials of known concentration	Thin film deposits of gaseous contaminants onto a detector substrate surface
Atomic force microscope	AFM		Shape and molecule size					Visual imaging
Wave-length dispersive X-ray spectroscopy	SEM-WDX	Measuring X-ray wave-length of elements of atomic number of lithium during SEM interaction; measuring X-ray wave-length elements > atomic number of lithium during SEM interaction	Element distribution can be combined with imaging tools (e.g. SEM, TEM, STEM)					Visual imaging

NOTE Resolution and sensitivity are interdependent parameters. Resolution is related to the concentration on the sample. Sensitivity can be influenced by optimizing the sample area.



## D.2.8 Indirect measurement methods (pre-treatment and measurement)

Table D.2 — Indirect measurement methods and their applications

Technique	Acronym	Principle	Information gained	Typical sensitivity	Typical quantitative analysis applications	
Thermal desorption–gas chromatography/mass spectrometry	TD-GC-MS	Contaminants on substrate surface are thermally desorbed and concentrated into a specific absorption column and analyte. Concentrates are then introduced to a gas chromatograph/mass spectrometer.	Quantified molecular	10 ng/m <sup>2</sup>	Quantified with standards	Trace analysis of organic species; evaluation of contaminants on silicon wafers (WTD GC-MS)
Solvent dissolution–ion chromatography/mass spectrometry	SD-IC/MS	Contaminants on substrate surface are dissolved in an appropriate solvent, via a concentration stage if required. An optimum amount of solution is then injected into an ion chromatograph/mass spectrometer.	Quantified ionic	10 ng/m <sup>2</sup>	Quantified with standards	Trace ionic contamination analysis; measurement of extractable ionic constituents of powders, encapsulation compounds and glasses, after sample preparation by reflux
Thermal desorption–ion mobility spectrometry	TD-IMS	Contaminants on substrate surface are thermally desorbed and are introduced to an ion mobility spectrometer. Contaminants are decomposed using $\beta$ rays into ionized fragments, which are separated according to their ion mobility. Ions are then determined with quadrupole mass detector.		parts per billion (ppb) in gas phase 1 µg/m <sup>2</sup>	Quantified with standards	Inorganic NH <sub>3</sub> and organic contaminants on substrate surface
Solvent dissolution–capillary electrophoresis–mass spectrometry	SD-CE/MS	The contaminants are dissolved by an appropriate solvent and are introduced into capillary electrophoresis (CE). The contaminants are separated from each other according to their conductive properties and evaluated by mass spectrometer.		200 ng/m <sup>2</sup>		



Table D.2 (continued)

Technique	Acronym	Principle	Information gained	Typical sensitivity	Typical quantitative analysis applications	
Solvent dissolution–high performance liquid chromatography	SD-HPLC	The contaminants are dissolved with appropriate solvent and are introduced to high-performance liquid chromatography to be separated from each other and evaluated.		2 000 ng/m <sup>2</sup>	Quantified with standards	Measurement of extractable organic components
Solvent dissolution–gas chromatography/mass spectrometry	SD-GC-MS	The contaminants on the substrate surface are dissolved with appropriate solvent. A portion of solvent is introduced to GC-MS.		500 ng/m <sup>2</sup> to 10,000 ng/m <sup>2</sup>		
Vapour phase decomposition–inductively coupled plasma/mass spectrometry	VPD-ICP/MS	Vapour-phase hydrofluoric acid (HF) is condensed on the surface to dissolve the SiO <sub>2</sub> with the contaminants in it. The HF with contamination forms a droplet on the resultant hydrophobic surface.  This is transferred by appropriate method to the measuring instrument ICP/MS.	Quantified elemental	1E-14 atoms/m <sup>2</sup>		Ultra trace analysis of metallic contaminants on silicon wafers

## D.2.9 Sampling, analysis and associated quality control (QC) elements

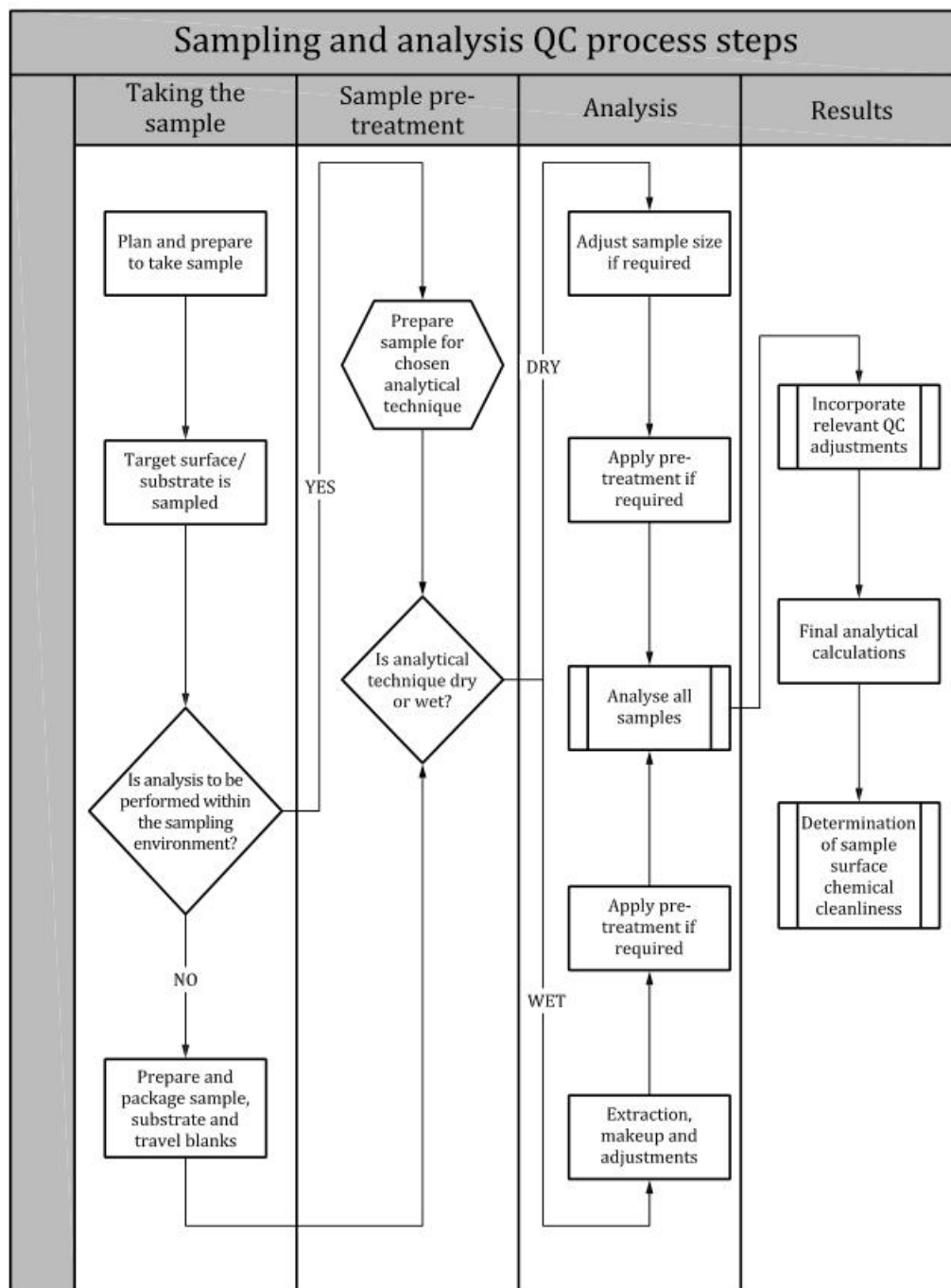
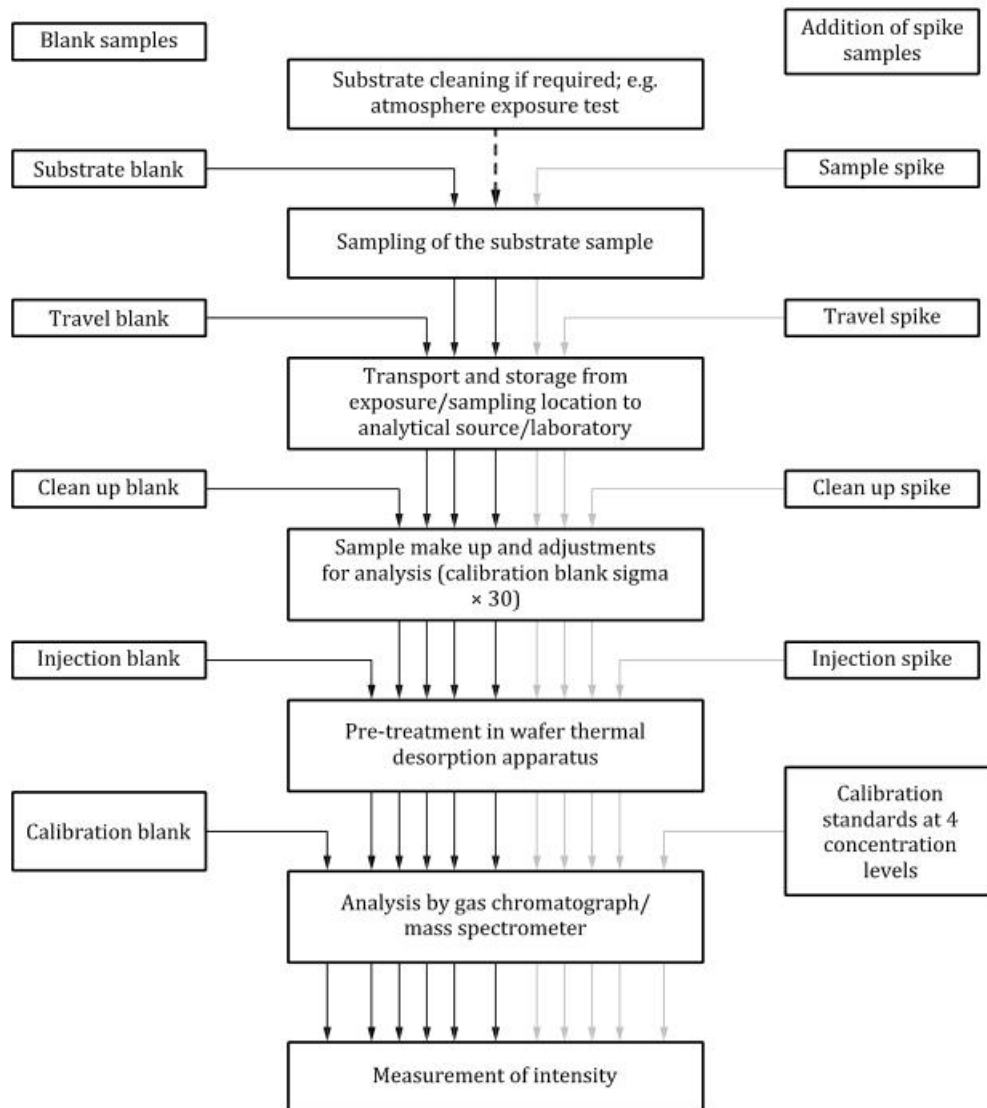


Figure D.3 — Overview flowchart of sampling, analysis and associated QC elements

### D.2.10 Analysis quality control



**Figure D.4 — Analysis quality control flowchart using silicon wafer TD-GC-MS**

In general, spike samples are introduced at critical sampling and analysis stages in order to monitor method performance or quantify the variance and bias of preparation and testing stages. The analysis method will describe spike levels at each stage. In this example of a silicon wafer, intensity and total ion chromatogram (TIC) of an injection spike analyte should be the same as that of the calibration standard, of the same amount added, within the required reliability range. For example, a 100-ng injection spike added to WTD is equivalent to a 100-ng calibration standard in intensity and TIC pattern (see Reference [9]).

## Annex E (informative)

### Test record documentation

[Table E.1](#) is an example of how a test report can be constructed. Other variations of the test report which are agreeable to both the customer and supplier may be used.

**Table E.1 — Supporting documentation for testing surface cleanliness by chemical concentration**

<b>Formalities</b> Title: Date: Tester: Customer:
<b>Environmental Conditions/ Cleanroom conditions</b> Temperature: Relative humidity: Locations used for the measurements:
<b>References of Standards and guidelines consulted:</b>
<b>Specimen</b> Description of the operating facility and identification:  Identification of the test object:
<b>Test set-up (photo and/or sketch)</b> Description of operating parameters: Description of measurement points and measurement methods:
<b>Measurement devices</b> Identification number of measuring device: Measurement range of measuring devices used; equipment resolution and detection limits:  Reference of calibration certificate:
<b>Performing the test</b> Test and measurement procedure: Noticeable observations made during the measurement where applicable:  Test duration and sampling time:
<b>Reference to ACC or nanoparticle measurements if applicable:</b>
<b>Results and analysis</b> Measurement values and / or their analysis:  Visual inspection of the test surfaces before and after the measurement , where applicable:



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